Wafer topography measurement by fast optical scanning deflectometry

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Abstract

Fast optical scanning deflectometry has been introduced for the measurement of the surface figure of optical surfaces. The measurement principle is based on physical ray tracing by means of a narrow laser beam deflected by an oscillating mirror and a large lens arranged for telecentric scanning. A new design of an instrument capable of measuring 12-inch wafers within 60 s and with a slope resolution better 1 μrad is presented.

This paper appears in the proceedings of the Lasers and Electro-Optics Europe, 2003 Conference (CLEO Europe 2003)
Publication Date: 22-27 June 2003
On page(s): 465-
ISSN:
ISBN: 0-7803-7734-6
INSPEC Accession Number: 8167861
Digital Object Identifier: 10.1109/CLEOE.2003.1313528
Current Version Published: 2004-07-26